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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		APPLICANT Steven Gerard Mayorga, et al.	
		FILING DATE	GROUP

(37 CFR 1.98(b))

10/02/99
12/21/01

U.S. PATENT DOCUMENTS

EXAM- INER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPRO- PRIATE
nm	5 0 2 8 5 6 6	7/2/91	Andre Lagendijk	437	238	7/27/90
	5 5 4 8 0 0 6	8/20/96	Satao Hirabayashi, et al	524	82	11/17/94
	5 3 8 0 8 1 2	1/10/95	Michael A. Lutz, et al	528	15	1/10/94
	3 3 4 4 1 1 1	9/26/67	Alan J. Chalk	260	46.5	9/26/66
	3 8 8 2 0 8 3	5/6/75	Abe Berger, et al	260	46.5	11/21/73

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
					YES NO
7 1 4 5 1 7 9	8/25/99	JP	C07F	7/21	X

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

nm	"User's Guide For: Glass Deposition With Teos," Dr. Arthur K. Hochberg, Schumacher, 1992.
	"Extrema® TOMCATS®, (Tetramethylcyclotetrasiloxane) Schumacher, 2000.
	"Modeling of Low-Pressure Deposition of SiO ₂ by Decomposition...", Huppertz, et al, Schumacher, 1979.
	"The Deposition of Silicon Dioxide Films at Reduced Pressure," Adams, et al, J. Electrochem Soc. 1979.
	"Preparation of Device-quality SiO ₂ Thin Films by Remote...", G. Lucovsky, Adv. Mat. Optics..., 1996.
	"Deposition of Silicon Oxide Films From TEOS By Low...", G. Tochtani, et al, J. Vac. Sci. Tech. A, 1993.
	"Properties of Silicon Dioxide Films Deposited at Low...", S K. Ray, et al, J. Vac. Sci. Tech. B, 1992.
	"Electron Cyclotron Resonance Microwave Discharge for Oxide...", J. Electrochem Soc. 1992.
	"Ion and Chemical Radical Effects on the Step Coverage...", C.-P. Chang, et al, J. Appl. Phys. 67, 1990.
	"Electron Cyclotron Resonance Microwave Discharge for Oxide...", C.S. Pai, et al, J. Appl. Phys. 1993
	"User's Guide For: Undoped Glass, PSG, and BPSG Using. ", Schumacher, 1991.
	"An Overview of the Polymerization of Cyclosiloxanes...", J.E. McGrath, et al, ACS Symp, 1983.

EXAMINER <i>Maat O Mac</i>	DATE CONSIDERED <i>3/11/03</i>
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EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.